



AF/IRW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Koji NOZAKI et al.

Group Art Unit: 1752

Serial No.: 10/623,679

Examiner: Amanda C. Walke

Filed: July 22, 2003

Confirmation No.: 5083

For: RESIST PATTERN THICKENING MATERIAL, RESIST PATTERN  
AND PROCESS FOR FORMING THE SAME, AND SEMICONDUCTOR  
DEVICE AND PROCESS FOR MANUFACTURING THE SAME

Attorney Docket Number: 030891

Customer Number: 38834

RESPONSE AFTER FINAL

**BOX: AF**

Commissioner for Patents

P. O. Box 1450

Alexandria, VA 22313-1450

Date: April 7, 2005

Sir:

In response to the Office Action dated January 25, 2005, Applicants argue as follows:

Remarks begin on page 2 of this paper.

DO NOT ENTER  
ACW 4/21/05